

Docket No.: 50212-211



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Kenichi ARIMURA, et al.

Serial No.: 09/807,902

Filed: April 19, 2001

Group Art Unit: 1763

Examiner: R. Bucker

For: WAFER SUPPORT IN SEMICONDUCTOR PRODUCTION APPARATUS

AMENDMENT

Commissioner for Patents
Washington, DC 20231

Sir:

#17B
3/8/02
MM
RECEIVED
MAR 06 2002
TC 1700

The following amendment and remarks are submitted in response to the Office

Action dated November 30, 2001.

IN THE CLAIMS

The claims are amended as follows:

1. A semiconductor production apparatus including a process chamber; a wafer support disposed within said process chamber for supporting a semiconductor wafer; and a heating source for heat treatment of the semiconductor wafer supported by said wafer support;

wherein said wafer support comprises a susceptor having an upper surface for mounting said semiconductor wafer thereon, and a susceptor support shaft for supporting said susceptor from thereunder; wherein said susceptor support shaft having a main shaft positioned substantially coaxial with a center of said susceptor, and at least three arms radially extending from an upper end of said main shaft, each said arm having a distal

B1

Sub
DI